
International Electrotechnical Commission IEC/TC47 Delft Conference Report

Description of conference

The TC47/WG4 meeting was held in the city of Delft in the Netherlands on October 28, 2003.

Three proposals for international standardization

Three representatives from Japan attended the IEC/TC47 (International Electrotechnical Commission Technical Committee Meeting No. 47) held in Delft in the Netherlands on October 28, 2003. In addition to participating in discussions concerning proposals for international standardization currently being put forth by Japan-standards for the terminology to be used for micromachines and MEMS, tensile testing methods for thin film materials, a proposal for international standardization developed from the results of the R&D for Standards Project conducted from 1999 until 2001, and standard specimens for testing-a report was also delivered on plans for fatigue testing of thin film materials to be performed as part of the energy usage management system standardization research survey begun this year, and a request was made for international cooperation in this regard. It was reported that these are the only three proposals being put forth at the present time by Japan in the field of nanotechnology materials.

Discussion of individual proposals

A discussion was held on comments submitted by Korea and China concerning the proposal for micromachine and MEMS terminology submitted by the Micromachine Center in July of 2002 now at the stage of a committee draft and it was decided that the terms would be prepared as a committee draft for vote. However it was requested that clarification be made of the scheduling of maintenance before a final draft for vote be written.

As for the two proposals concerning thin film materials tensile testing, these proposals had already been presented in July earlier this year, and while they had only been adopted as new proposals as of October 10, although there were

questions raised by British and American representatives about the English phrasing, in recognition of the fact that such questions were unrelated to the essence of the proposals, the representatives said that they would accept the proposals. Since this eliminated the basic problems, approval was given to proceed on to the next step of developing a committee draft and it was decided that Japan would submit a draft in March 2004. Both proposals thereby advanced a single step further towards approval.

Holding of a new WG meeting

The Korean delegation proposed that a WG meeting be held in June 2004 in Geneva or Phoenix to discuss the creation of generic specifications for MEMS. The stated purpose of this meeting would be to start to establish a position for lists of technical terms, tensile testing methods, fatigue testing methods, and other MEMS standards to be developed in the future. The Japanese delegation expressed its agreement with this proposal and it was decided that the WG meeting would be held.

Persons in attendance

The persons who attended the meeting are as listed below:

R. Turner (*Convenor, UK KBCI*)

Kuniki Owada

(*International Standardization Engineering Laboratory*)

Akira Umeda

(*Japan, National Institute of Advanced Industrial Science and Technology*)

M. Konno (*Japan, Micromachine Center*)

Sekwang Park

(*Korea, Kyungpook National University*)

Sang-Geun Lee

(*Korea, Agency for Technology and Standards*)

Bo Cui

(*China, Hebei Semiconductor Research Institute*)

Miao Lu

(*China, Hebei Semiconductor Research Institute*)